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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/905,172	·	07/13/2001	David S. Mui	004227 USA 02/ETCH/SILICO	2748
32588	7590	07/02/2004	EXAMINER		INER
APPLIED	MATERI	ALS, INC.		DEO, DUY V	U NGUYEN
2881 SCOT	T BLVD.	M/S 2061			
SANTA CLARA, CA 95050			ART UNIT	PAPER NUMBER	
	•			1766	

DATE MAILED: 07/02/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)					
Advisory Action	09/905,172	MUI ET AL.					
Advisory Action	Examiner	Art Unit					
	DuyVu n Deo	1765					
The MAILING DATE of this communication appe	ars on the cover sheet with the c	orrespondence address	;				
THE REPLY FILED 14 June 2004 FAILS TO PLACE THE Therefore, further action by the applicant is required to a final rejection under 37 CFR 1.113 may only be either: (1 condition for allowance; (2) a timely filed Notice of Appearamentation (RCE) in compliance with 37 CFR 1.114.	void abandonment of this applice  I) a timely filed amendment whi	cation. A proper reply t ch places the application	to a on in				
PERIOD FOR RE	PLY [check either a) or b)]						
a) The period for reply expires 3 months from the mailing date of b) The period for reply expires on: (1) the mailing date of this Adv event, however, will the statutory period for reply expire later the ONLY CHECK THIS BOX WHEN THE FIRST REPLY WAS 706.07(f).	isory Action, or (2) the date set forth in th an SIX MONTHS from the mailing date o FILED WITHIN TWO MONTHS OF THI	f the final rejection. E FINAL REJECTION. See N	MPEP				
Extensions of time may be obtained under 37 CFR 1.136(a). The dath have been filed is the date for purposes of determining the period of extens 37 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened (b) above, if checked. Any reply received by the Office later than three mo earned patent term adjustment. See 37 CFR 1.704(b).	sion and the corresponding amount of the statutory period for reply originally set in	efee. The appropriate extension the final Office action; or (2) a	on fee under as set forth in				
1. A Notice of Appeal was filed on Appellant's 37 CFR 1.192(a), or any extension thereof (37 CFI	•						
2. The proposed amendment(s) will not be entered be	ecause:						
(a) ☐ they raise new issues that would require further consideration and/or search (see NOTE below);							
(b) ☐ they raise the issue of new matter (see Note below);							
(c) they are not deemed to place the application in better form for appeal by materially reducing or simplifying the issues for appeal; and/or							
(d) ☐ they present additional claims without canceling a corresponding number of finally rejected claims. NOTE:							
3. Applicant's reply has overcome the following reject	tion(s):		<i>'</i>				
4. Newly proposed or amended claim(s) would canceling the non-allowable claim(s).	be allowable if submitted in a s	eparate, timely filed an	nendment				
5. ☐ The a) ☐ affidavit, b) ☐ exhibit, or c) ☐ request fo application in condition for allowance because: See		sidered but does NOT p	place the				
6. The affidavit or exhibit will NOT be considered berraised by the Examiner in the final rejection.	gause it is not directed SOLELY	to issues which were r	newly				
7. For purposes of Appeal, the proposed amendment explanation of how the new or amended claims we			l an				
The status of the claim(s) is (or will be) as follows:							
Claim(s) allowed:							
Claim(s) objected to:							
Claim(s) rejected: <u>1-11, 13-40</u> .							
Claim(s) withdrawn from consideration:	_						
The drawing correction filed on is a) □ approved or b) □ disapproved by the Examiner.							
9. Note the attached Information Disclosure Stateme	nt(s)( PTO-1449) Paper No(s).	·					
10.□ Other:							

Continuation of 5. does NOT place the application in condition for allowance because: Referring to applicant's argument that the office action does not explain why one skill I the art would be motivated to select this particular material for use in Huang, as opposed to the myriad other low k dielectric constant organic layers known in the art, one skill in the art can use other low k dielectric organic layers too As shown by Huang, any low k dielectric can be used including this low k dielectric organic material from Hasegawa.

In response to applicant's argument that the examiner's conclusion of obviousness is based upon improper hindsight reasoning it must be recognized that any judgment on obviousness is in a sense necessarily a reconstruction based upon hindsight reasoning. Bu so long as it takes into account only knowledge which was within the level of ordinary skill at the time the claimed invention was made, and does not include knowledge gleaned only from the applicant's disclosure, such a reconstruction is proper. See In re McLaughlin, 44 F.2d 1392, 170 USPQ 209 (CCPA 1971).

Hasegawa does suggest PECVD (col. 9, line 9). Any process that is available to one skill in the art, including PECVD, for depositing organic layer, would be obvious.

Referring to applicant's argument that a layer useful as an interlayer insulating material would by no means provide a reasonable expectation that the same material can be successfully employed as a masking layer, this does not response to the rejection because it is combined not as a masking layer. Furthermore, the low k organic layer is not a masking layer in the claims but a part of a multiplayer structure that called masking structure by the applicant. It is obvious that any structure that has the same layers would also read on claimed masking structure.

Referring to applicant's argument that the office action motivation of adding the low k material form Hasegawa is an suggestion of "obvious to try" of using one of the low k dielectric layer taught in Hasegawa as an masking layer as taught in Huang. First, there is n obvious to try. Huang does teach using a low k organic material and the layer taught by Hasegawa is a low k organic material. Therefore, it would be used with an expectation of success. Second, the low k organic material is not combined as a masking layer but Hasegawa further shows the specific organic material that is silent in Huang.